	Hits	Search Text	DBs
15	0	(((organic or polymer$4 or polyimide or polyamide or photoresist or resist) near22 (conduct$4 or electroconductive or semiconduct$4 or transistor)) same (dop$4 or implant$4 or infus$3) same (irradiat$4 or expos$4 or illuminat$4) same ((electron near9 beam) or e$3beam or UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (((dop$4 or implant$6 or infus$4) near22 (UV or irradiat$4 or radiation or expos$4)) same (interconnect$4 or ((organic or polymer$3 or region) near19 (interconnect or connect$4 or contact$4))) same source same drain) and ((remov$4 or eliminat$4 or dissipat$$ or rid or bounce) near18 (unbounded or mobile or loose$3 or (weak near9 (implant or dop$4))) near29 (((temperature or heat$3 or bak$4 or anneal) near4 (high$3 or elevat$4 or ris$3)) or ((reduc$4 or vacuum or evacuu$5) near3 (pressure or torr or atmosphere))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	0	((remov$4 or eliminat$4 or dissipat$$ or rid or bounce) near18 (((unbounded or mobile or loose$3) near8 (implant$4 or dop$4)) or (weak near9 (implant or dop$4))) near29 (((temperature or heat$3 or bak$4 or anneal) near4 (high$3 or elevat$4 or ris$3)) or ((reduc$4 or vacuum or evacuu$5) near3 (pressure or torr or atmosphere)))) and (((organic or polymer$4 or polyimide or polyamide or photoresist or resist) near22 (conduct$4 or electroconductive or semiconduct$4 or transistor)) same (dop$4 or implant$4 or infus$3) same (irradiat$4 or expos$4 or illuminat$4) same ((electron near9 beam) or e$3beam or UV or IR or DUV or EUV or excimer or laser or light or radiation))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	11	((remov$4 or eliminat$4 or dissipat$$ or rid or bounce or strip$$) near18 (((unbounded or mobile or loose$3 or peripher$5 or surface) near8 (implant$4 or dop$4)) or (weak near9 (implant or dop$4))) near29 (((temperature or heat$3 or bak$4 or anneal) near4 (high$3 or elevat$4 or ris$3)) or ((reduc$4 or vacuum or evacuu$5) near 3 (pressure or torr or atmosphere)))) and (((organic or polymer$4 or polyimide or polyamide or photoresist or resist) near22 (conduct$4 or electroconductive or semiconduct$4 or transistor)) same (dop$4 or implant$4 or infus$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
18	101	((remov$4 or eliminat$4 or dissipat$$ or rid or bounce or strip$$) near18 (((unbounded or mobile or loose$3 or peripher$5 or surface or (low near3 diffus$5)) near8 (implant$4 or dop$4)) or (weak near9 (implant or dop$4))) near29 ((temperature or heat$3 or bak$4 or anneal) or ((reduc$4 near4 pressure) or vacuum or evacuu$5))) and (((organic or polymer$4 or polyimide or polyamide or photoresist or resist) near22 (conduct$4 or electroconductive or semiconduct$4 or transistor)) same (dop$4 or implant$4 or infus$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	90	S18 NOT S17	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
20	46	((organic or polymide or photoresist) near16 (semiconduct$4 or conduct$4) near22 (dop$3 or implant$4 or infus$4) near16 contact$4 near9 source near12 drain near9 electrode)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
22	38	((organic or polymide) near16 (semiconduct$4 or conduct$4) near22 (dop$3 or implant$4 or infus$4) near26 contact$4 near20 source near16 drain)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB